

FIG. 1
PRIOR ART

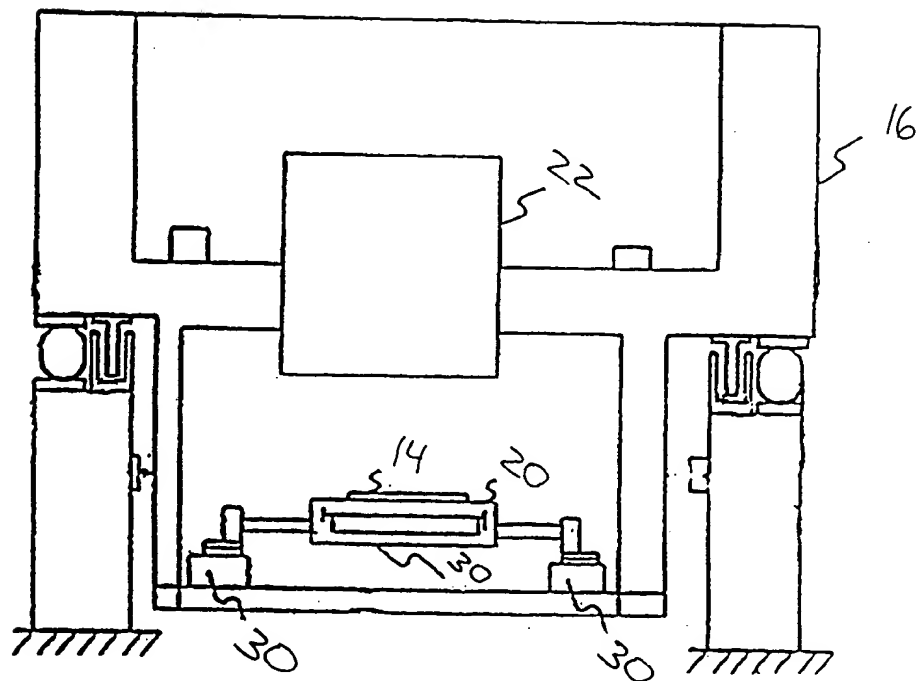


FIG. 2
PRIOR ART

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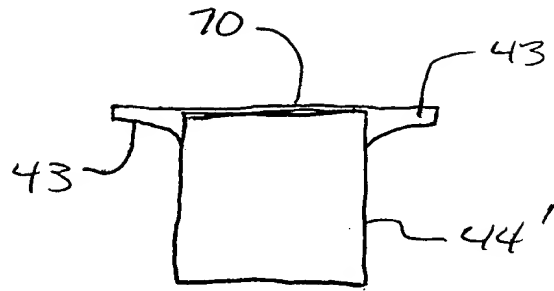


FIG. 3(A)

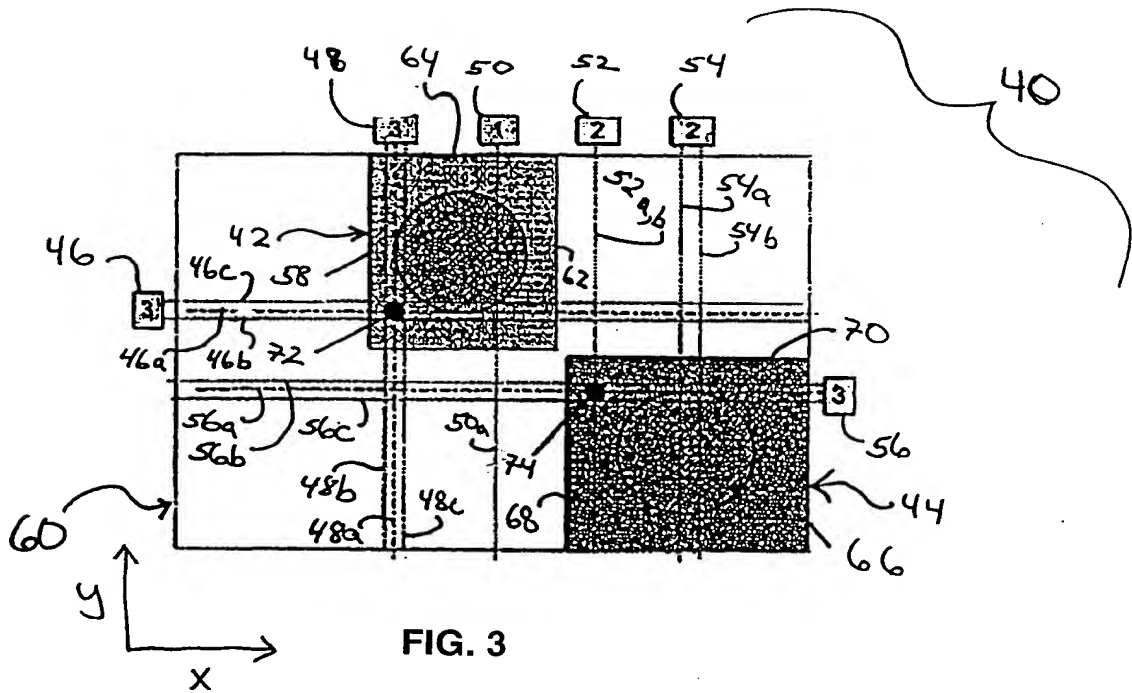


FIG. 3

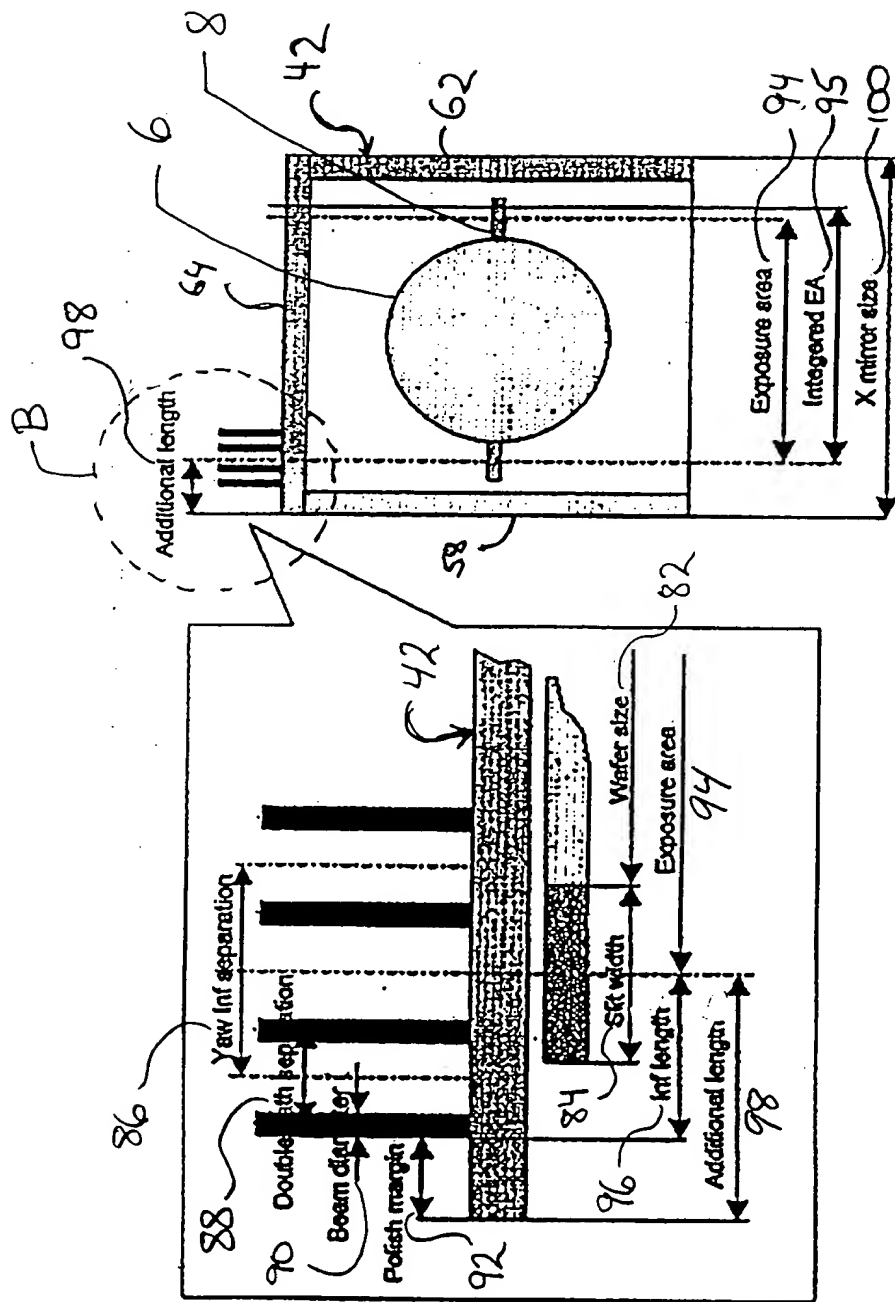


FIG. 4(B)

FIG. 4(A)

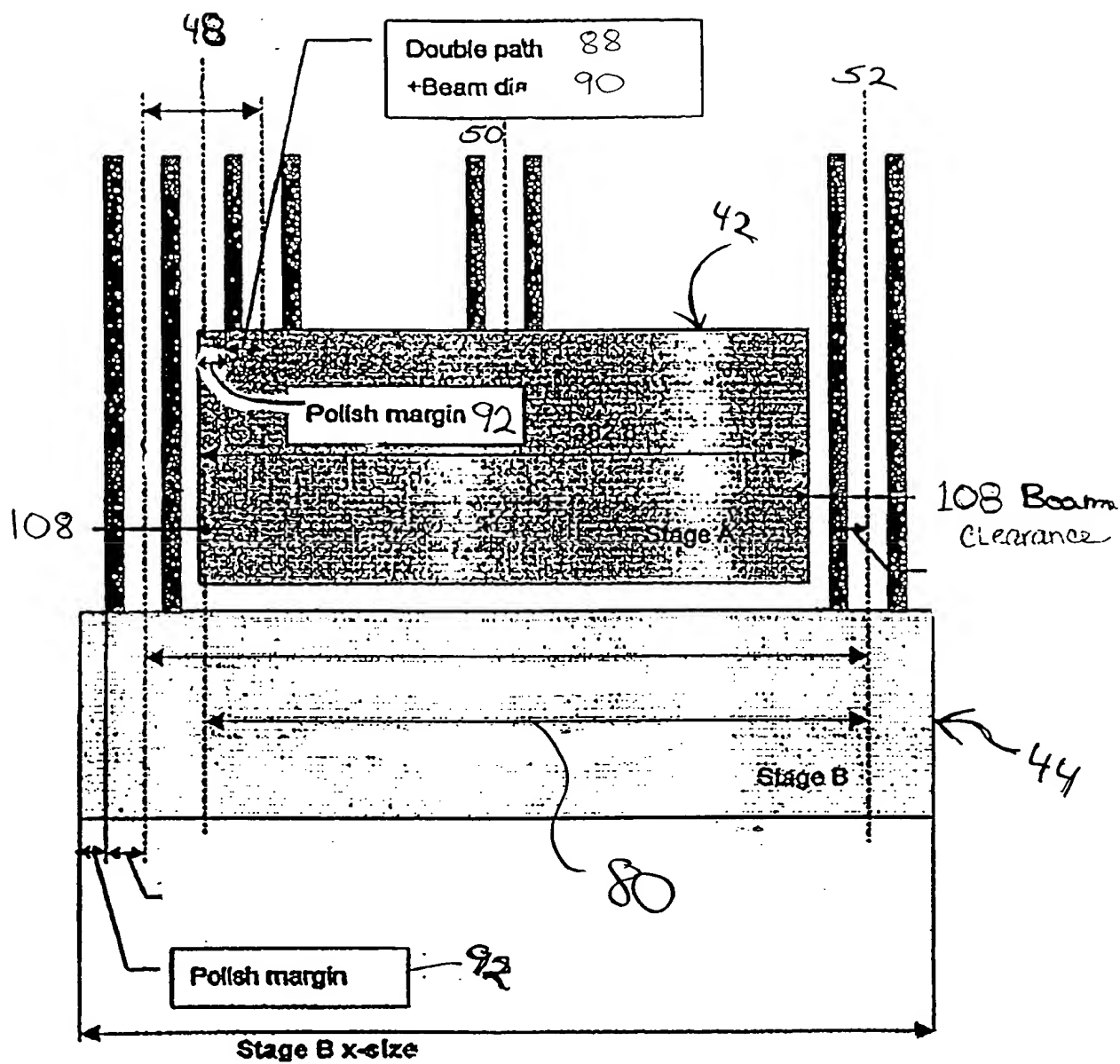


FIG. 5

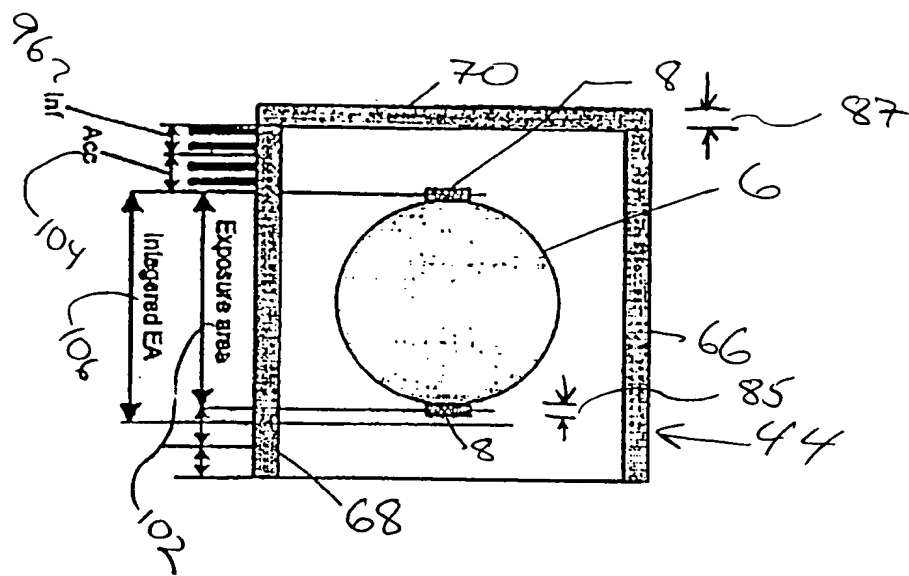


FIG. 6

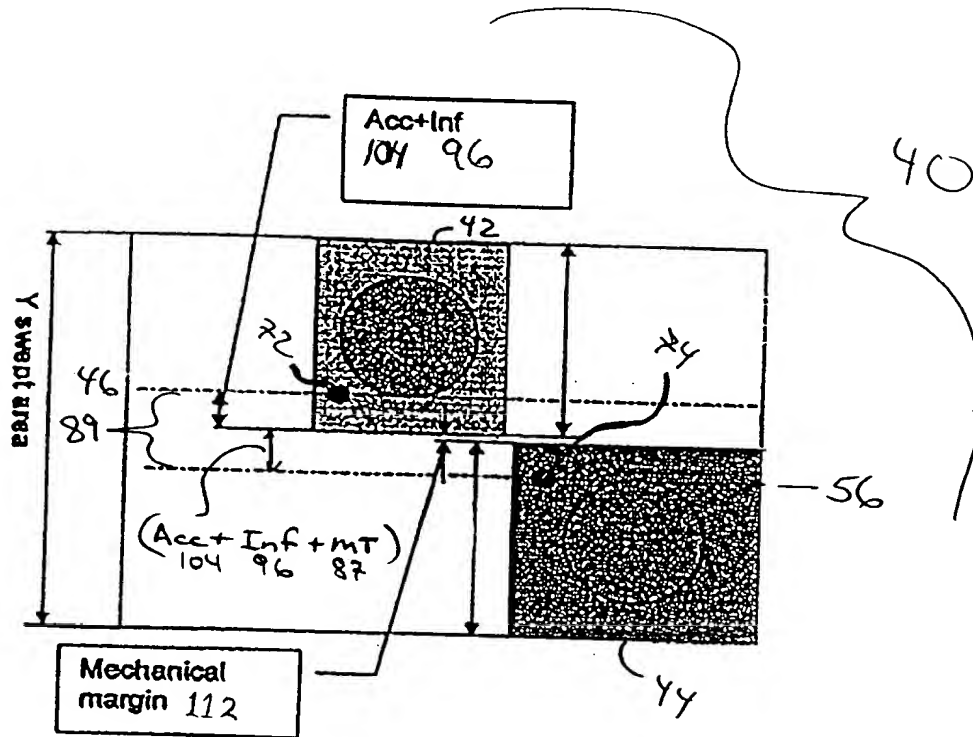


FIG. 7

FIG. 9

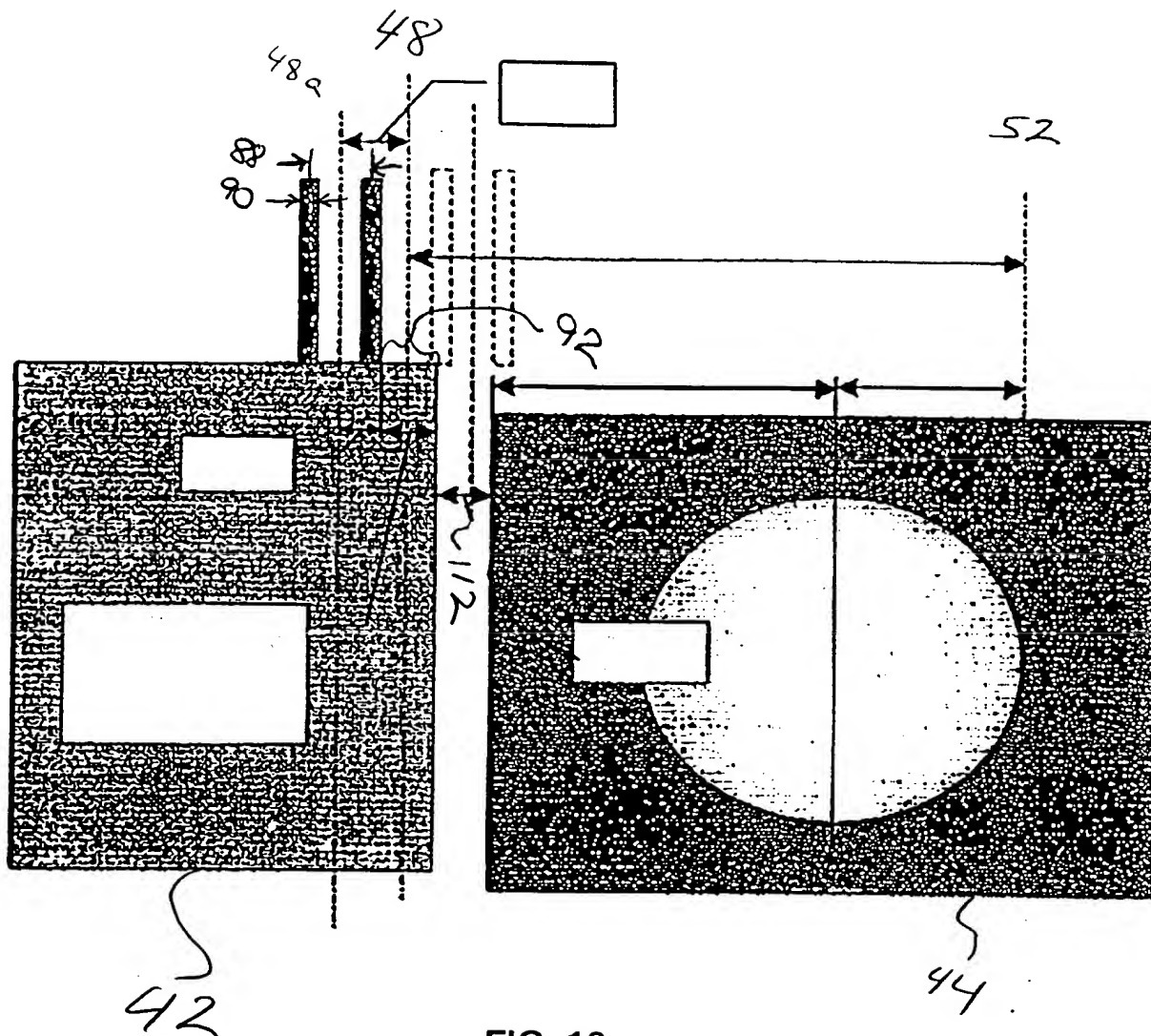


FIG. 10

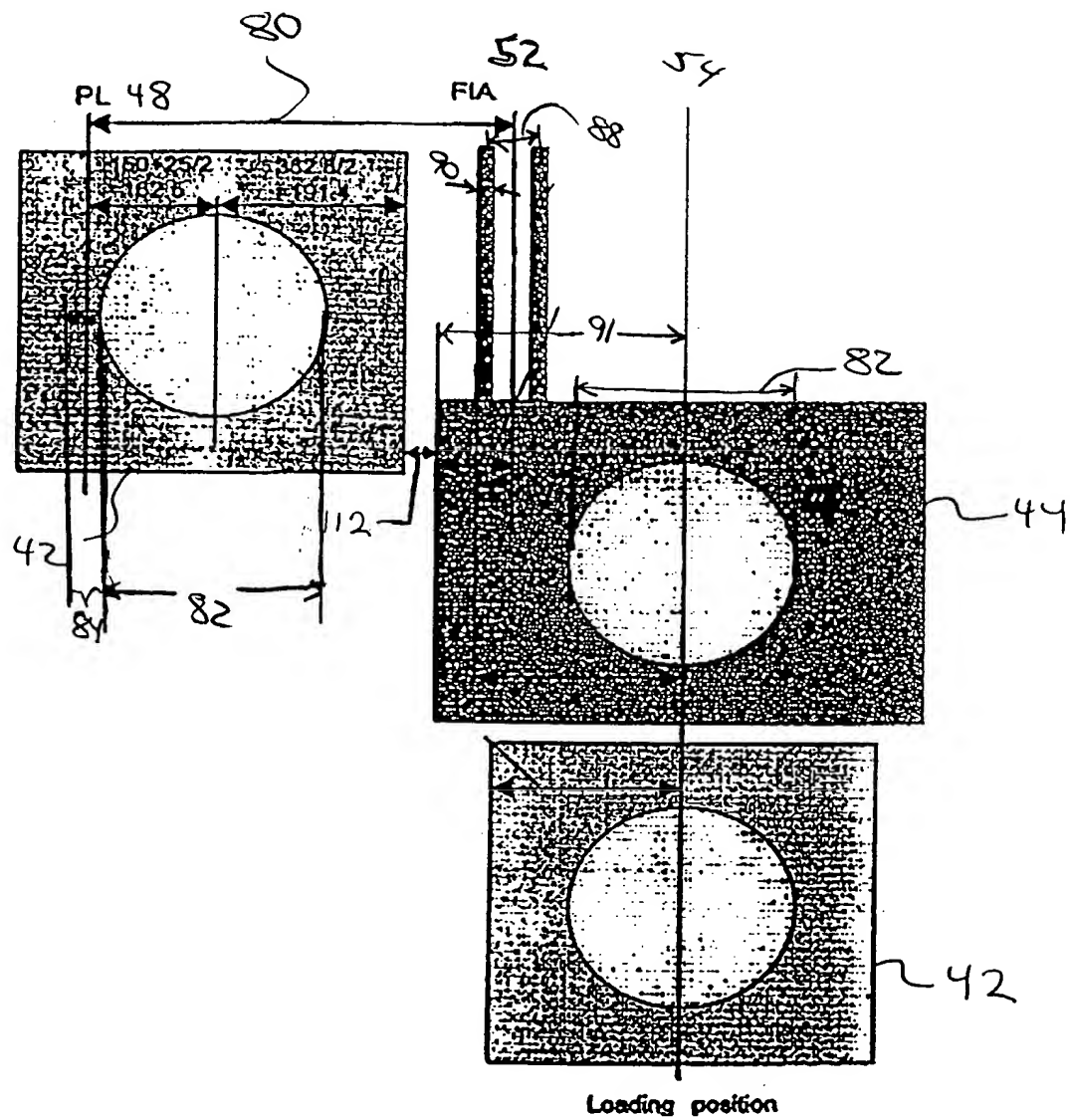


FIG. 11

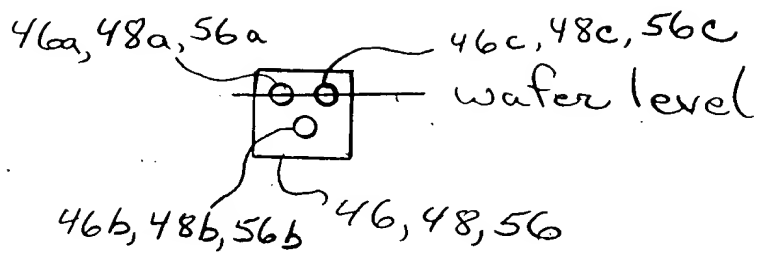


FIG. 12(A)

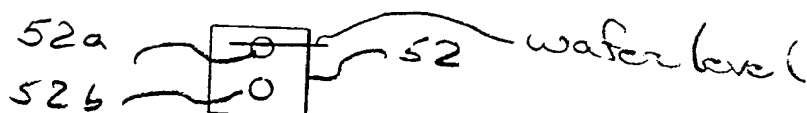


FIG. 12(B)



FIG. 12(C)

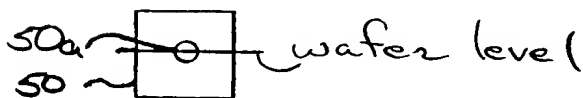


FIG. 12(D)

200

Wafer stage 42: Start EGA. Change to monitor Y position by 52 and Yaw by 56. Halt movement when necessary to avoid disturbing stage 44.

202

Wafer stage 44: Continue exposing if loaded.
See Fig. 14(b)

Wafer stage 42: Continue EGA. Change to monitor Y position by 50.
 Wafer stage 44: Stopped at the end of the exposure sequence.
 See Fig. 14(c)

204

Wafer stage 42: End EGA. Begin switching in the Y direction.
Change to monitor Yaw by 52 and 50.
Wafer stage 44: Switch in the Y direction.
See Fig. 14(d)

206

Wafer stage 42: Switch in the Y direction. Change to monitor X position by 56a.
 Wafer stage 44: Wait to switch in the Y direction. Change to monitor Y position by 56c when 56c becomes available.
 See Fig. 14(e)

208

Wafer stage 42: Wait in the Y direction. Change to monitor X position by 46 and Yaw by 46 when 46 becomes available.
 Wafer stage 44: Switch in the Y direction.
 See Fig. 14(f)

210

Wafer stage 42: Switch in the Y direction.
 Wafer stage 44: Switch in the Y direction. Change to monitor X position by 56 and Yaw by 56.
 See Fig. 14(g)

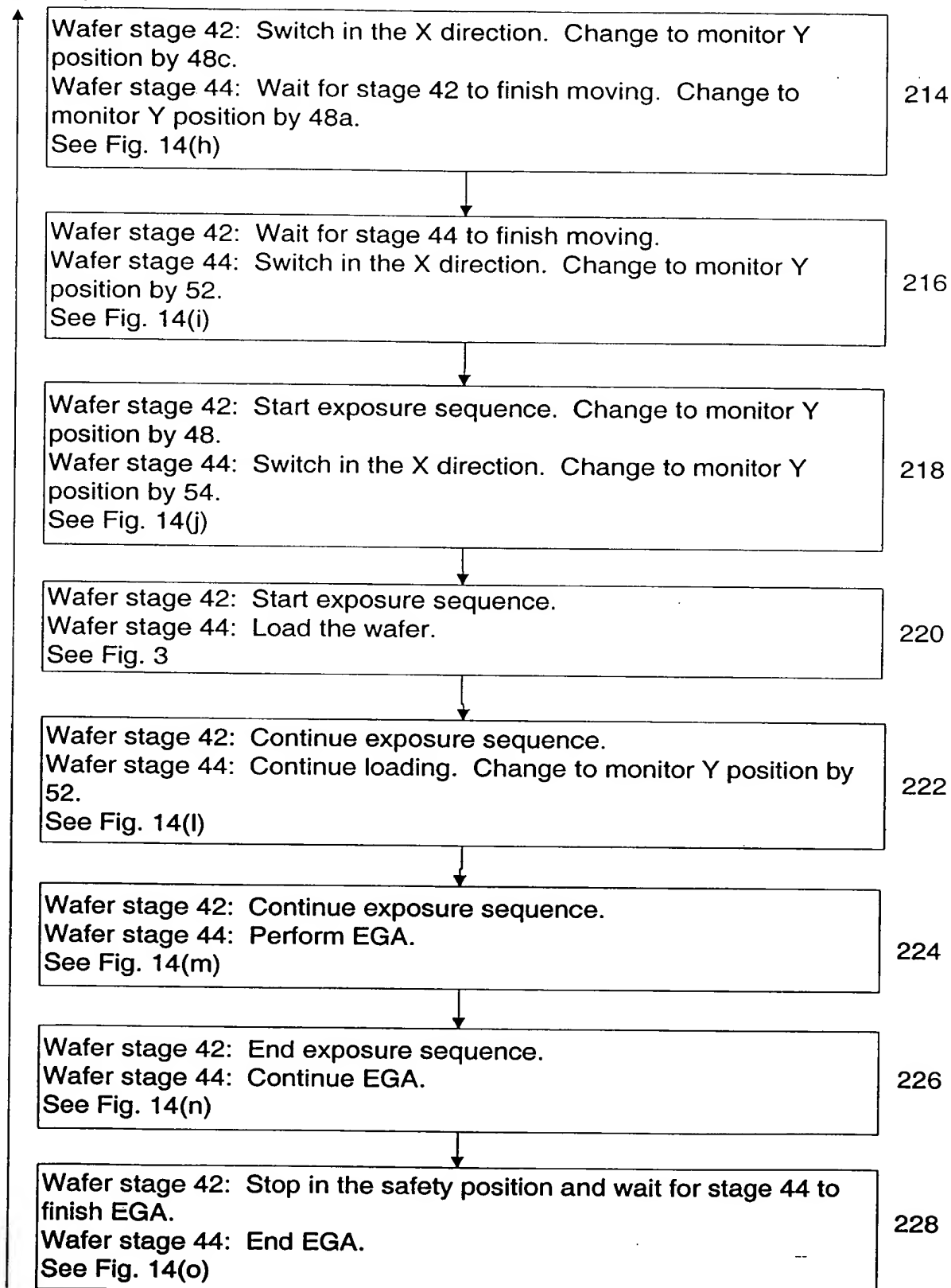
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To Fig. 13(b)

From Step 243

FIG. 13(A)

To Fig. 13(a)
and step 200



To Fig. 13(c)

FIG. 13(B)

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To Fig. 13(a)
and step 200

From Fig. 13(b) and step 228

Wafer stage 42: Stop in the safety position.
Wafer stage 44: Switch in the X direction.
See Fig. 14(p)

230

Wafer stage 42: Switch in the X direction. Change to monitor Y position by 50.
Wafer stage 44: Wait for 48a to become available to control Y position. Resume switching in the X direction.
See Fig. 14(q)

232

Wafer stage 42: Continue switching in the X direction.
Wafer stage 44: Wait in the switch X/wait position. Change to monitor Y position by 48a.
See Fig. 14(r)

234

Wafer stage 42: Continue switching in the X direction. Change to monitor Y position by 52.
Wafer stage 44: Wait in the switch X/wait position. Change to monitor Y position by 48 and Yaw by 48.
See Fig. 14(s)

236

Wafer stage 42: Continue switching in the X direction. Change to monitor Y position by 54 and Yaw by 54.
Wafer stage 44: Wait in the switch X/wait position.
See Fig. 14(t)

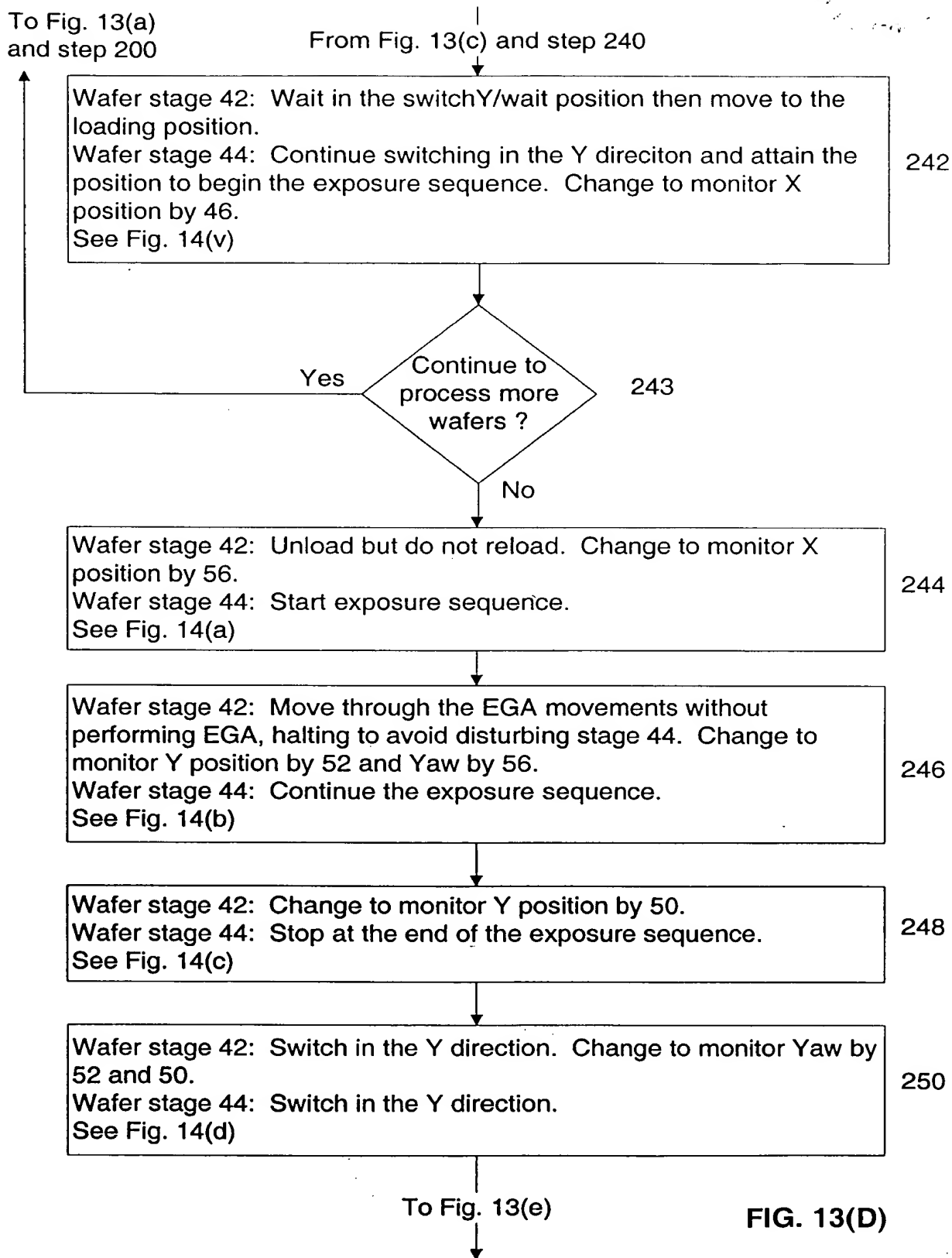
238

Wafer stage 42: Switch in the Y direction. Change to monitor X position by 56a.
Wafer stage 44: Switch in the Y direction. Change to monitor X position by 56c.
See Fig. 14(u)

240

To Fig. 13(d)

FIG. 13(C)



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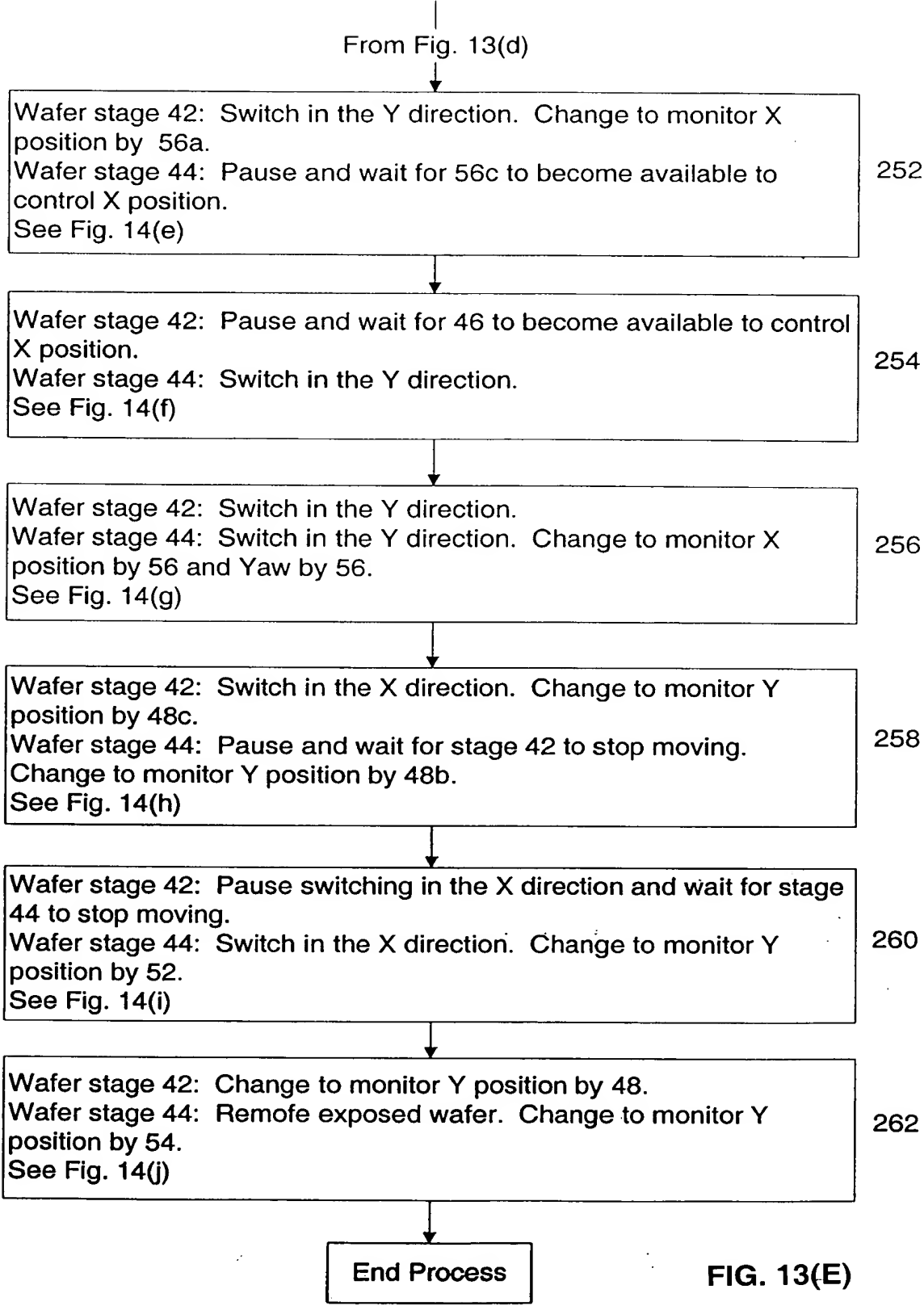


FIG. 13(E)

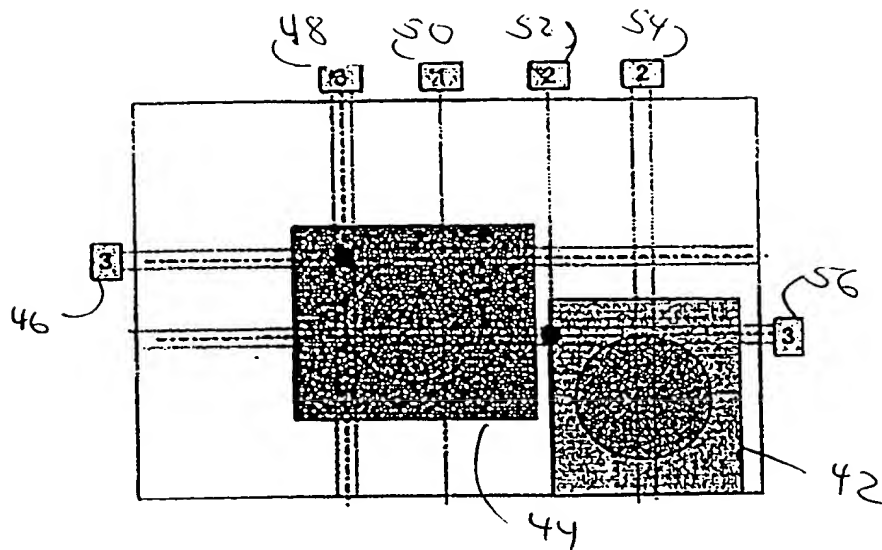


FIG. 14(A)

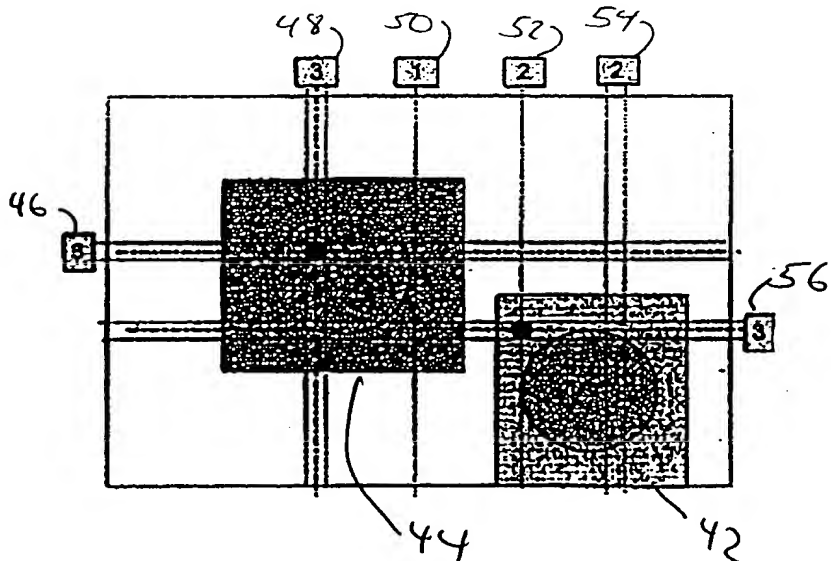


FIG. 14(B)

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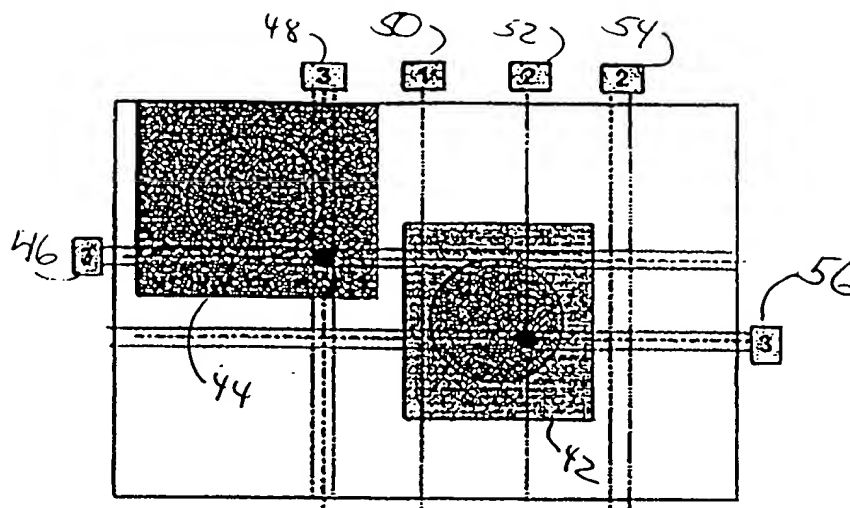


FIG. 14(C)

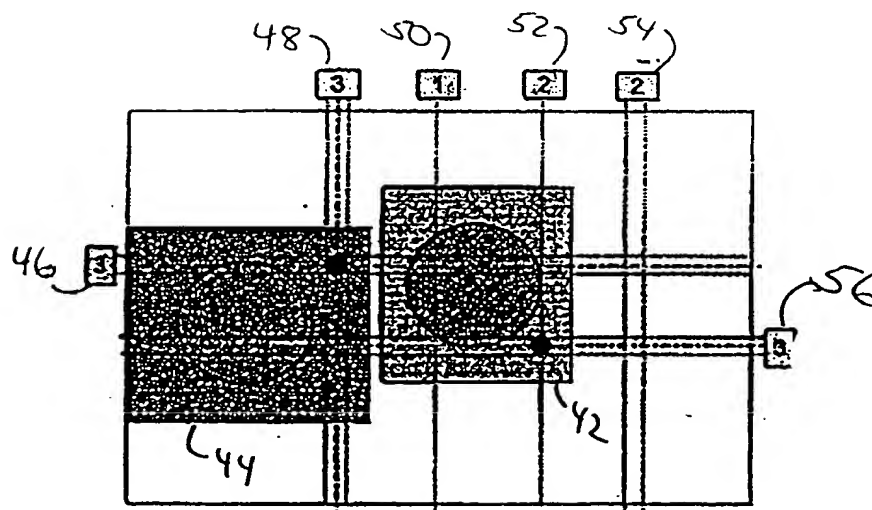


FIG. 14(D)

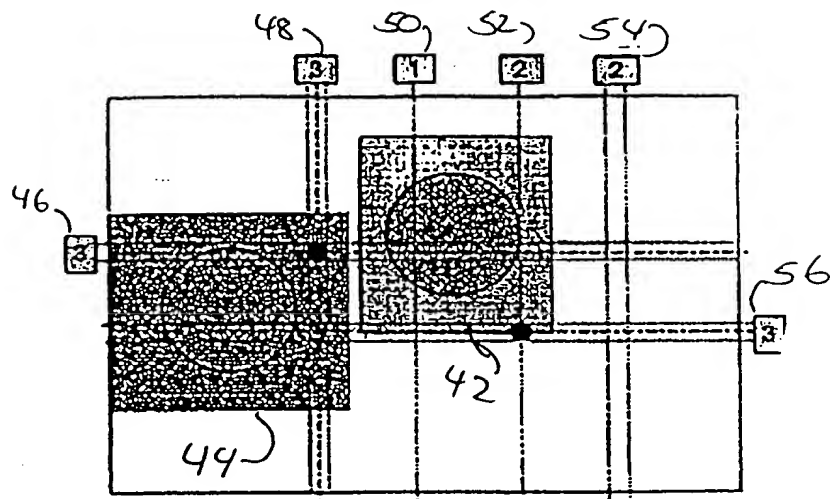


FIG. 14(E)

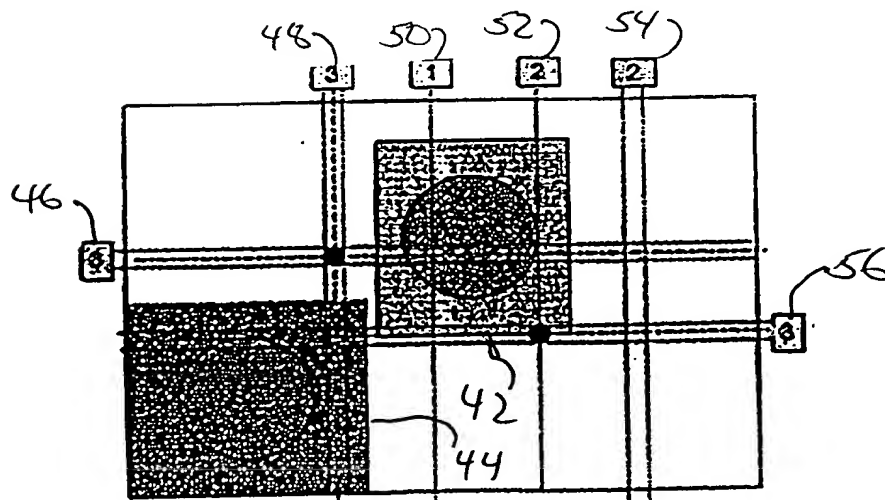


FIG. 14(F)

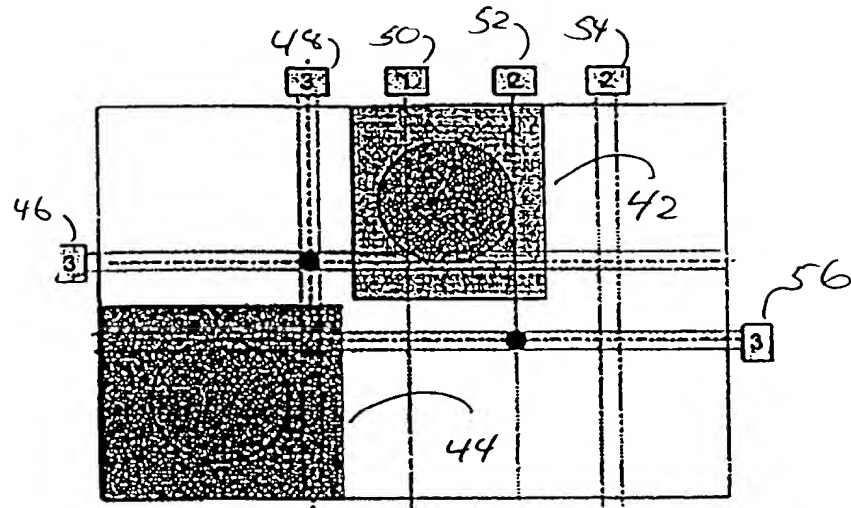


FIG. 14(G)

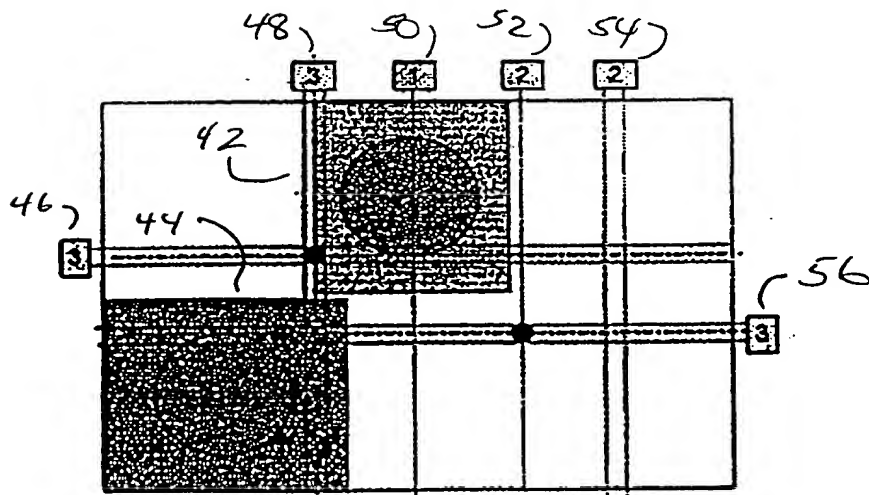


FIG. 14(H)

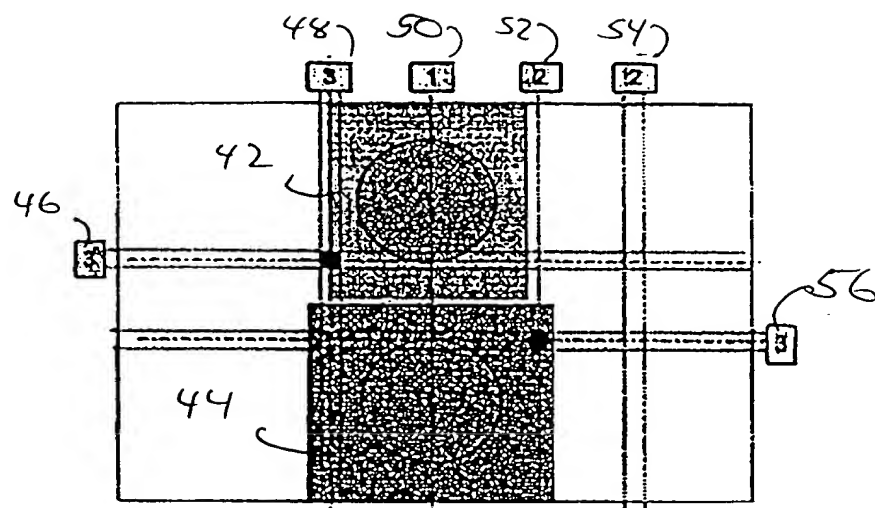


FIG. 14(I)

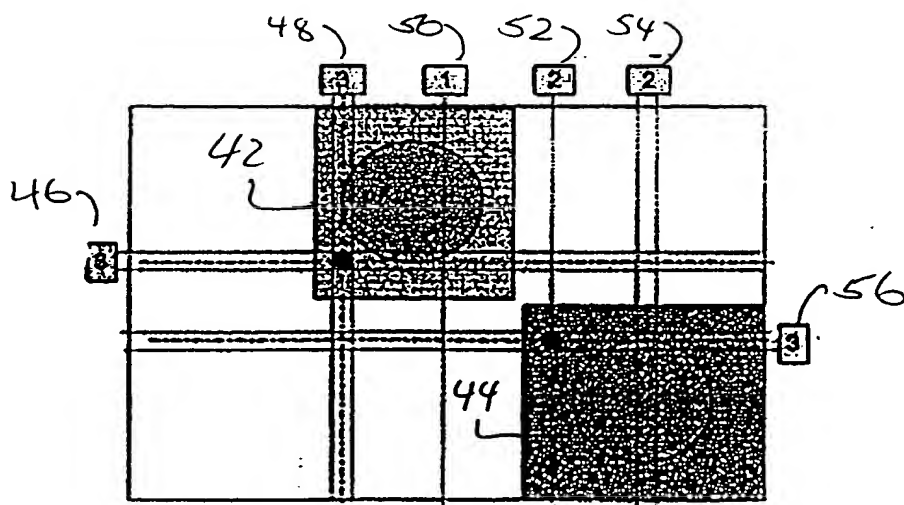


FIG. 14(J)

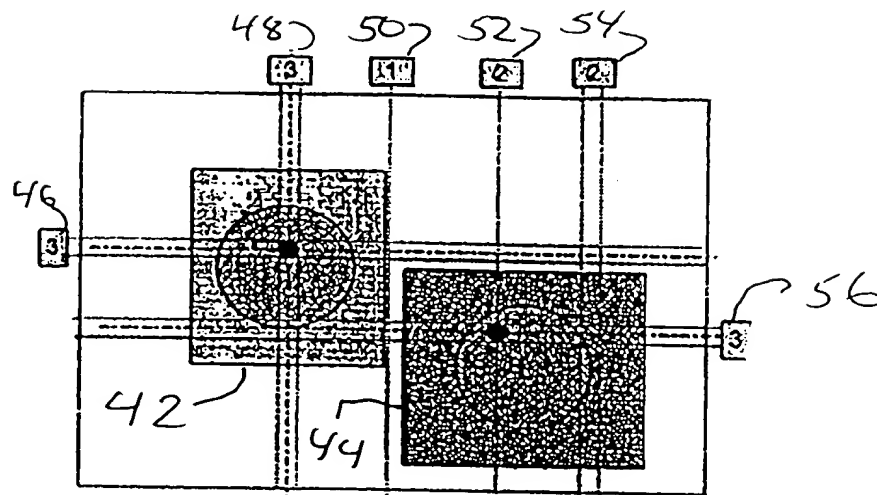


FIG. 14(M)

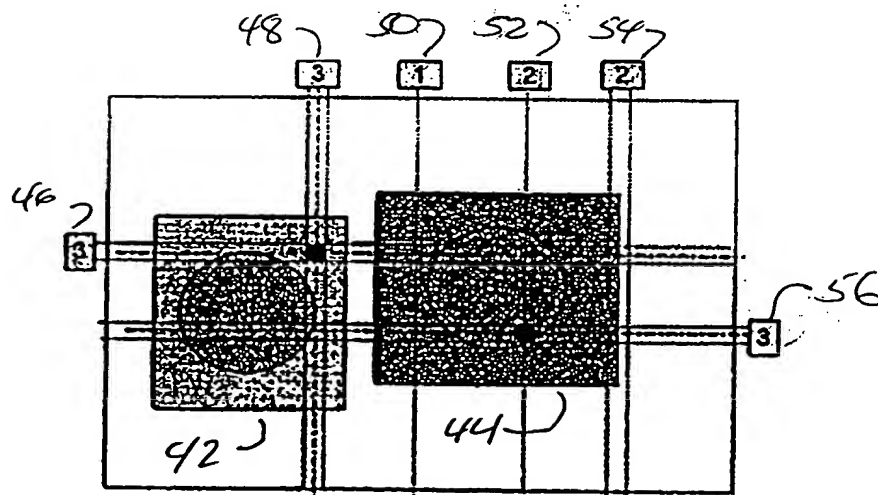


FIG. 14(N)

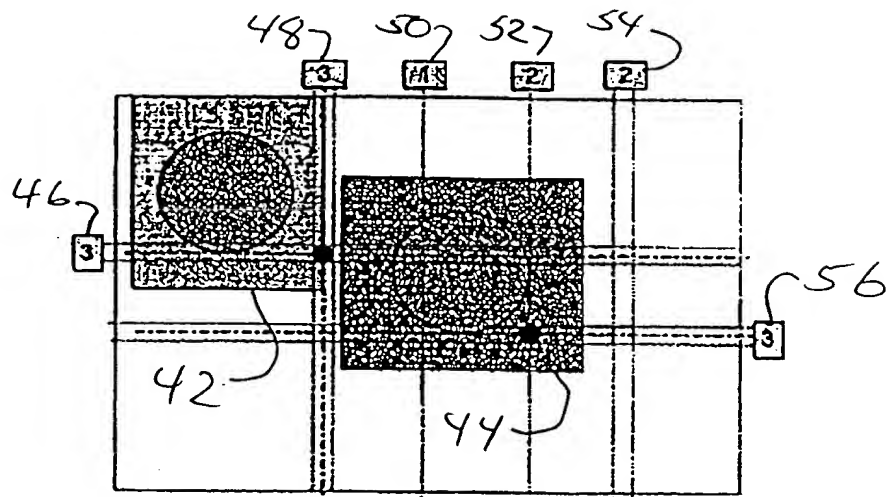


FIG. 14(O)

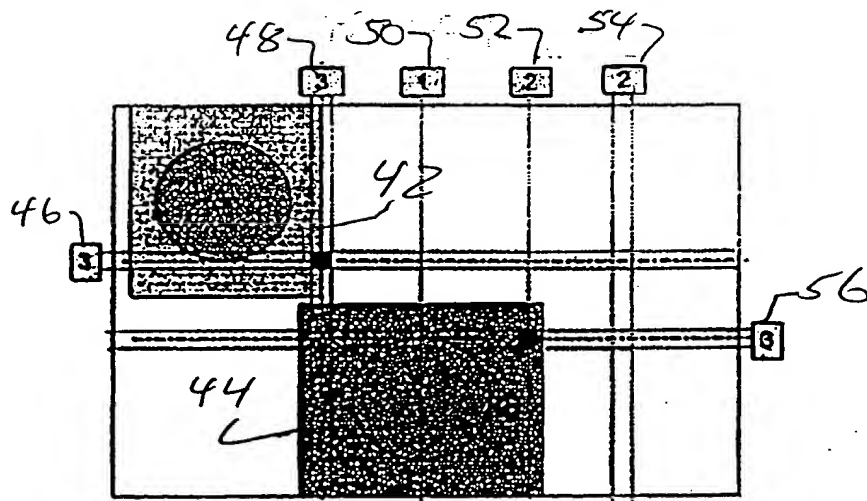


FIG. 14(P)

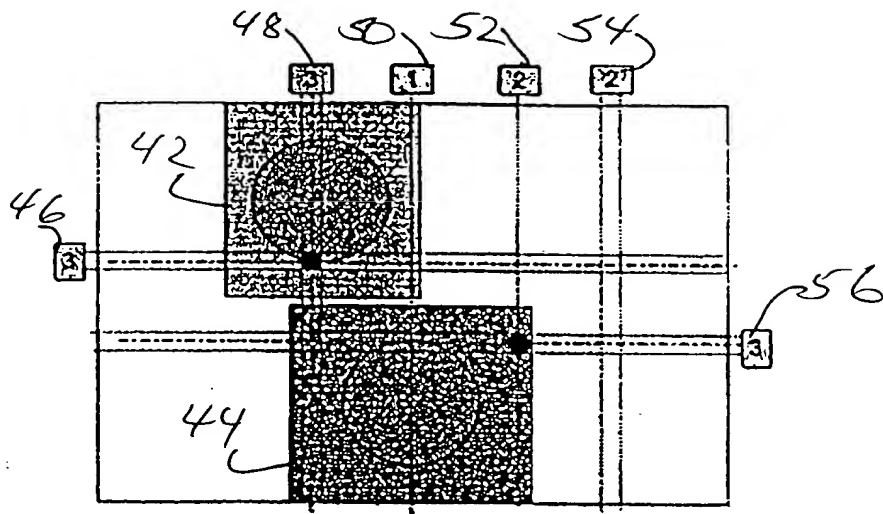


FIG. 14(Q)

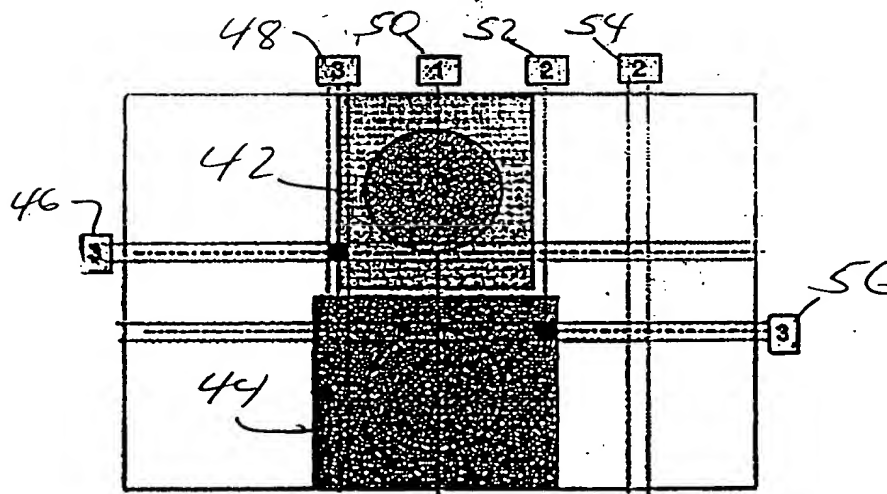


FIG. 14(R)

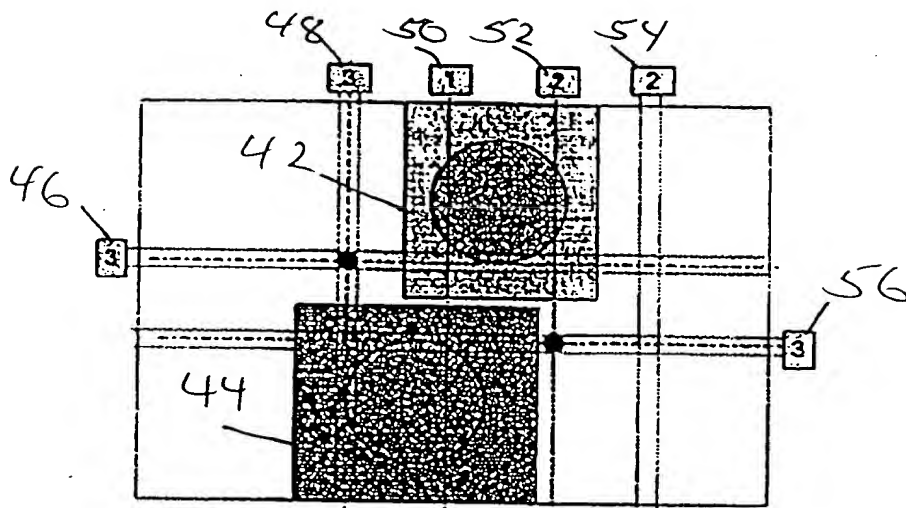


FIG. 14(S)

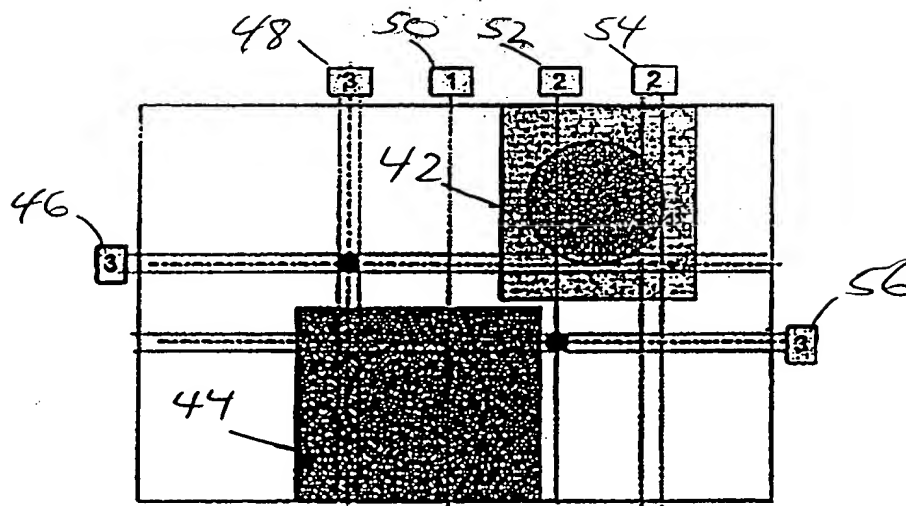


FIG. 14(T)

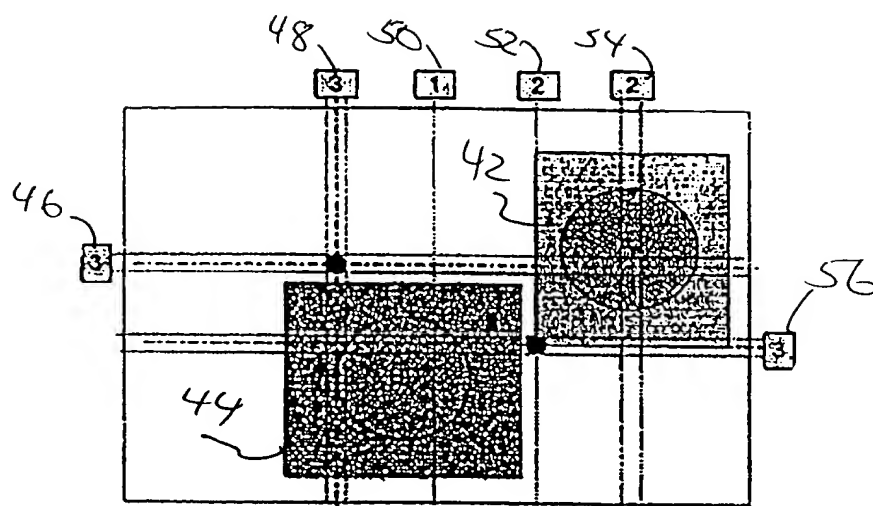


FIG. 14(U)

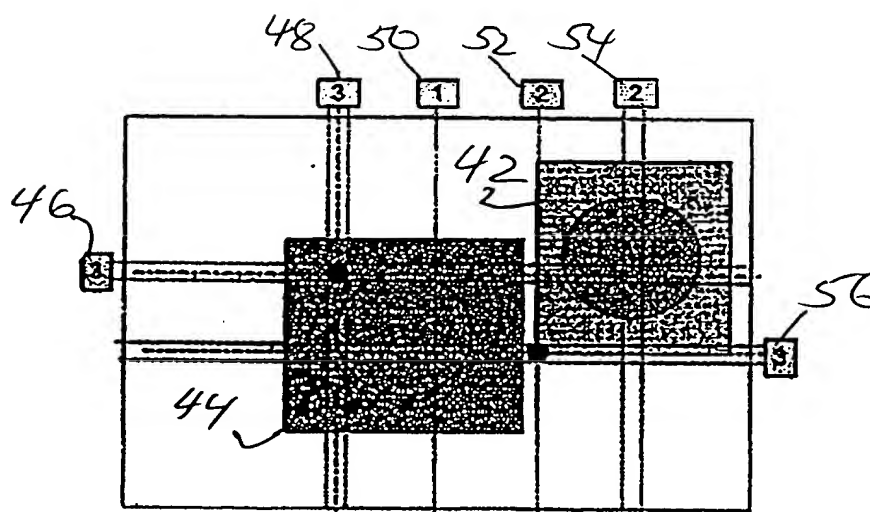


FIG. 14(V)